

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 2001-105733

(43)Date of publication of application : 17.04.2001

(51)Int.Cl.

B41M 5/26

(21)Application number : 11-288763

(71)Applicant : RICOH CO LTD

(22)Date of filing : 08.10.1999

(72)Inventor : TATEWAKI TADAFUMI
FURUYA HIROMI
KAWAMURA FUMIO

(54) METHOD FOR MANUFACTURING REVERSIBLY THERMALLY RECORDING MEDIUM

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a method for manufacturing a reversibly thermally recording medium without appearing a skin fog by an erasing device such as an erasing bar or a thermal head, and to further provide a reversibly thermally recording medium capable of being rapidly erased and having good durability without notch on the medium.

SOLUTION: A reversely thermally recording medium has a reversibly thermally recording layer containing a reversibly heat sensitive composition, includes an electron donative colorational compound, an electron acceptive compound and a third component on at least a support, and is capable of forming a relatively color developing state due to a difference of a heating temperature and/or cooling speed after heating. A drying temperature when the layer is manufactured is a melting point or higher of the third component contained in the layer and melting points or lower of the electron donative colorational and acceptive compounds.

LEGAL STATUS

[Date of request for examination] 22.03.2004

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the
examiner's decision of rejection or application
converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

Copyright (C); 1998,2003 Japan Patent Office